

VIA EFS

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In Re Patent Application:	Luca Pusterla, et al.	§	
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Conf. No.:	7623	§	Group Art Unit: 1743
		§	
Appln. No.:	10/601,383	§	Examiner: Yelena G. Gakh
		§	
Filing Date:	June 23, 2003	§	Atty. Docket No.: 6023-169US
		§	(BX2453M)
Title:	METHOD FOR MEASURING THE CONCENTRATION OF IMPURITIES IN HELIUM BY ION MOBILITY SPECTROMETRY		

**AMENDMENT**

This is in response to the Office Action dated December 1, 2006 (Paper No. 20061027) in the above-identified patent application. This response is being timely filed by March 1, 2007. Please amend the application, without prejudice, as follows: